



# Beam Initiative

## The Fine Line: Spring 2018 Videos for the eBeam Community

### Shot Talk: A Word from Our Sponsor

Aki Fujimura, CEO of D2S, highlights several hot topics from this year's SPIE Conference—EUV shot noise, neuromorphic computing, nanoimprint lithography (NIL), multi-beam mask writing, eBeam direct write, and rising interest in deep learning.



A Japanese version of the video can be found [here](#). Leo Pang, chief product officer of D2S, also recaps these developments in [Chinese](#).



### Tech Talk

From the 10<sup>th</sup> eBeam Initiative luncheon event at SPIE, Hiroshi Matsumoto of NuFlare Technology provides an overview of inline pixel-level dose correction (PLDC) for the NuFlare MBM-1000 multi-beam mask writer.

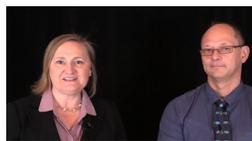


Also at the eBeam Initiative event at SPIE, Sergey Babin of aBeam Technologies presents on new developments in CD-SEM metrology.



### Perspectives

Laurent Pain of Leti celebrates 50 years of innovation at Leti and reviews key topics from Leti's new workshop at SPIE, including maskless eBeam lithography, directed self-assembly (DSA) and full-wafer NIL.



### Video Archive

#### The Fine Line: Autumn 2017 Edition



Shot Talk:  
[Aki Fujimura, D2S](#)



Shot Talk:  
[Leo Pang, D2S](#)



Tech Talk:  
[Tom Faure, GLOBALFOUNDRIES](#)



Perspectives:  
[Jed Rankin, GLOBALFOUNDRIES](#)

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The eBeam Initiative provides a forum for educational and promotional activities regarding new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please email [requests@ebeam.org](mailto:requests@ebeam.org) or visit [www.ebeam.org](http://www.ebeam.org)